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Technology and challenges for extreme ultraviolet lithography

Monday, 17 September 2018 16:20 (45 minutes)

ASML is an important player in the semiconductor industry. Using lithography, small structures are being written on wafers resulting in the active devices as we know them from servers, PCs and mobile phones.

In my talk I will sketch the technological challenges which ASML faces mechanical, electronical, and optical and sketch the progress over the last 30 years. The talk concentrates on the upcoming technology where EUV (extreme ultraviolet light at 13.5 nm) is being used for lithography.

Summary

Presenter: WIM, Van Der Zande

Session Classification: Invited